

## **AZ 1518 – run sheet**

Merck (AZ Electronic Materials)

[nanyte.com/photoresists/az-1518](https://nanyte.com/photoresists/az-1518) · last updated 2026-07-26

**Thickness:** 1.9–5.6  $\mu\text{m}$

**Softbake:** 100 °C (90–110 °C) · 1.5 min · hotplate

**Exposure dose:** 150 mJ/cm<sup>2</sup> @ 436 nm

**Post-exposure bake:** 105–115 °C

**Develop:** Developer AZ 300MIF · Time 60 s · Method puddle

**Hardbake:** 100–110 °C